

John S Villarrubia

List of Publications by Year in descending order

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papers

3,001
citations

430874

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43
g-index

73
all docs

73
docs citations

73
times ranked

2143
citing authors

#	ARTICLE	IF	CITATIONS
1	Algorithms for scanned probe microscope image simulation, surface reconstruction, and tip estimation. <i>Journal of Research of the National Institute of Standards and Technology</i> , 1997, 102, 425.	1.2	568
2	Nanoindentation of polymers: an overview. <i>Macromolecular Symposia</i> , 2001, 167, 15-44.	0.7	413
3	Morphological estimation of tip geometry for scanned probe microscopy. <i>Surface Science</i> , 1994, 321, 287-300.	1.9	272
4	Nitric oxide adsorption, decomposition, and desorption on Rh(100). <i>Journal of Chemical Physics</i> , 1987, 87, 750-764.	3.0	146
5	Formation of Si(111)-(1 \times 1)Cl. <i>Physical Review B</i> , 1990, 41, 9865-9870.	3.2	137
6	Experimental test of blind tip reconstruction for scanning probe microscopy. <i>Ultramicroscopy</i> , 2000, 85, 141-153.	1.9	130
7	Scanning-tunneling-microscopy study of the Si(111)-7 \times 7 rest-atom layer following adatom removal by reaction with Cl. <i>Physical Review Letters</i> , 1989, 63, 306-309.	7.8	118
8	Identification of the Products from the Reaction of Chlorine with the Silicon(111)-(7 \times 7) Surface. <i>Science</i> , 1990, 248, 838-840.	12.6	97
9	Scanned probe microscope tip characterization without calibrated tip characterizers. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 1996, 14, 1518.	1.6	94
10	Scanning electron microscope measurement of width and shape of 10 nm patterned lines using a JMONSEL-modeled library. <i>Ultramicroscopy</i> , 2015, 154, 15-28.	1.9	83
11	The populations of bridge and top site CO on Rh(100) vs coverage, temperature, and during reaction with O. <i>Journal of Chemical Physics</i> , 1987, 87, 6710-6721.	3.0	78
12	Scanning electron microscope dimensional metrology using a model-based library. <i>Surface and Interface Analysis</i> , 2005, 37, 951-958.	1.8	69
13	Determination of optimal parameters for CD-SEM measurement of line-edge roughness. , 2004, 5375, 515.		62
14	Blind estimation of general tip shape in AFM imaging. <i>Ultramicroscopy</i> , 2008, 109, 44-53.	1.9	47
15	Unbiased estimation of linewidth roughness. , 2005, 5752, 480.		44
16	Observation of significant nitrogen-oxygen bond weakening in nitric oxide on Rh(100). <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1986, 4, 1487-1490.	2.1	43
17	Multidetector electron energy-loss spectrometer for time-resolved surface studies. <i>Review of Scientific Instruments</i> , 1988, 59, 22-44.	1.3	43
18	Scanning electron microscope analog of scatterometry. , 2002, 4689, 304.		35

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19	CO adsorption site occupations on Fe(111) vs coverage and temperature: The kinetics of adsorption and reaction. <i>Journal of Chemical Physics</i> , 1989, 90, 2050-2062.	3.0	33
20	Simulation study of repeatability and bias in the CD-SEM. , 2003, , .		31
21	Monte Carlo modeling of secondary electron imaging in three dimensions. , 2007, , .		31
22	Dimensional metrology of resist lines using a SEM model-based library approach. , 2004, 5375, 199.		29
23	General three-dimensional image simulation and surface reconstruction in scanning probe microscopy using a dixel representation. <i>Ultramicroscopy</i> , 2007, 108, 29-42.	1.9	26
24	Sensitivity of scanning electron microscope width measurements to model assumptions. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2009, 8, 033003.	0.9	24
25	Intercomparison of SEM, AFM, and electrical linewidths. , 1999, , .		22
26	Edge determination for polycrystalline silicon lines on gate oxide. , 2001, , .		19
27	Electron Inelastic Mean Free Paths for LiF, CaF ₂ , Al ₂ O ₃ , and Liquid Water from 433 keV down to the Energy Gap. <i>ACS Omega</i> , 2020, 5, 4139-4147.	3.5	18
28	Influence of focus variation on linewidth measurements. , 2005, , .		15
29	Simulation study of repeatability and bias in the critical dimension scanning electron microscope. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2005, 4, 033002.	0.9	15
30	New insights into subsurface imaging of carbon nanotubes in polymer composites via scanning electron microscopy. <i>Nanotechnology</i> , 2015, 26, 085703.	2.6	15
31	Three-Dimensional (3D) Nanometrology Based on Scanning Electron Microscope (SEM) Stereophotogrammetry. <i>Microscopy and Microanalysis</i> , 2017, 23, 967-977.	0.4	13
32	Increasing the value of atomic force microscopy process metrology using a high-accuracy scanner, tip characterization, and morphological image analysis. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 1996, 14, 1540.	1.6	12
33	Toward nanometer accuracy measurements. , 1999, 3677, 1017.		12
34	Sensitivity of SEM width measurements to model assumptions. , 2009, , .		12
35	10nm three-dimensional CD-SEM metrology. <i>Proceedings of SPIE</i> , 2014, , .	0.8	12
36	Advanced metrology needs for nanoelectronics lithography. <i>Comptes Rendus Physique</i> , 2006, 7, 931-941.	0.9	11

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37	Image simulation and surface reconstruction of undercut features in atomic force microscopy. , 2007, , .		11
38	Comparison of Electron Imaging Modes for Dimensional Measurements in the Scanning Electron Microscope. Microscopy and Microanalysis, 2016, 22, 768-777.	0.4	11
39	Issues in Line Edge and Linewidth Roughness Metrology. AIP Conference Proceedings, 2005, , .	0.4	9
40	Can we get 3D-CD metrology right?. , 2012, , .		9
41	The effect of tip size on the measured Ra of surface roughness specimens with rectangular profiles. Precision Engineering, 2014, 38, 217-220.	3.4	9
42	Optimizing hybrid metrology: rigorous implementation of Bayesian and combined regression. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 044001.	0.9	9
43	On Low-Energy Tail Distortions in the Detector Response Function of X-Ray Microcalorimeter Spectrometers. Journal of Low Temperature Physics, 2020, 199, 1046-1054.	1.4	9
44	<title>Electrical test structures replicated in silicon-on-insulator material</title>. , 1996, , .		8
45	Strategy for faster blind reconstruction of tip geometry for scanned probe microscopy. , 1998, 3332, 10.		8
46	<title>Linewidth measurement intercomparison on a BESOI sample</title>. , 2000, 3998, 84.		8
47	CD-SEM measurement line edge roughness test patterns for 193 nm lithography. , 2003, 5041, 127.		7
48	Scanning electron microscopy imaging of ultra-high aspect ratio hole features. , 2012, , .		7
49	Summary Abstract: The kinetics of CO dissociation on Fe(111). Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1987, 5, 538-539.	2.1	6
50	3D Monte Carlo modeling of the SEM: Are there applications to photomask metrology?. , 2014, , .		6
51	Progress on accurate metrology of pitch, height, roughness, and width artifacts using an atomic force microscope. , 1995, , .		5
52	Advanced electron microscopy needs for nanotechnology and nanomanufacturing. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2005, 23, 3015.	1.6	5
53	Virtual rough samples to test 3D nanometer-scale scanning electron microscopy stereo photogrammetry. Proceedings of SPIE, 2016, 9778, .	0.8	5
54	<title>Grating pitch measurements with the molecular measuring machine</title>. , 1999, 3806, 46.		4

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55	Proximity-associated errors in contour metrology. , 2010, , .		4
56	Optimizing hybrid metrology: rigorous implementation of Bayesian and combined regression. Proceedings of SPIE, 2015, , .	0.8	4
57	Research Update: Electron beam-based metrology after CMOS. APL Materials, 2018, 6, .	5.1	4
58	Conventional vs. model-based measurement of patterned line widths from scanning electron microscopy profiles. Ultramicroscopy, 2019, 206, 112819.	1.9	4
59	Tip Characterization for Dimensional Nanometrology. Nanoscience and Technology, 2004, , 147-168.	1.5	4
60	New way of handling dimensional measurement results for integrated circuit technology. , 2003, 5038, 508.		3
61	Probing Electrified Liquid-Solid Interfaces with Scanning Electron Microscopy. ACS Applied Materials & Interfaces, 2020, 12, 56650-56657.	8.0	3
62	Line edge roughness characterization of sub-50nm structures using CD-SAXS: round-robin benchmark results. , 2007, , .		2
63	Developing a method to determine linewidth based on counting the atom spacings across a line. , 1998, 3332, 441.		1
64	Tip characterization for scanning probe microscope width metrology. , 1998, , .		1
65	Line Edge Roughness and Cross Sectional Characterization of Sub-50 nm Structures Using Critical Dimension Small Angle X-ray Scattering. AIP Conference Proceedings, 2007, , .	0.4	1
66	Linewidth roughness and cross-sectional measurements of sub-50 nm structures with CD-SAXS and CD-SEM. Proceedings of SPIE, 2008, , .	0.8	1
67	Accurate and traceable dimensional metrology with a reference CD-SEM. , 2008, , .		1
68	Comparison of Secondary, Backscattered and Low Loss Electron Imaging for Dimensional Measurements in the Scanning Electron Microscope. Microscopy and Microanalysis, 2015, 21, 1105-1106.	0.4	1
69	Comparison of Secondary, Backscattered and Low Loss Electron Imaging for Dimensional Measurements in the Scanning Electron Microscope - Part 2. Microscopy and Microanalysis, 2016, 22, 608-609.	0.4	1
70	An a Posteriori Error Estimate for Scanning Electron Microscope Simulation with Adaptive Mesh Refinement. Journal of Scientific Computing, 2019, 80, 1700-1715.	2.3	1
71	Summary Abstract: Kinetics of the adsorption and reaction of H2 and O2 on nickel(110). Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1984, 2, 1019-1020.	2.1	0
72	Linewidth Roughness and Cross-sectional Measurements of Sub-50 nm Structures Using CD-SAXS and CD-SEM. IEEE International Symposium on Semiconductor Manufacturing Conference, Proceedings, 2008, , .	0.0	0

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73	An accurate Monte Carlo sampler for electron elastic scattering angular distributions between 50 eV and 300 keV. <i>Microscopy and Microanalysis</i> , 2021, 27, 1322-1323.	0.4	0